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Form PTO-1449
(Rev. 8-83)U.S. Department of Commerce
Patent and Trademark Office

Atty. Docket No.: 0756-1930

Serial No. 09/239,948

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Applicant: Shunpei YAMAZAKI et al.

Filing Date: 01/29/99

Group: 2811

U.S. PATENT DOCUMENTS

Examiner Initial	Patent Number	Issue Date	Patentee	Class	Subclass	Filing Date (if approp.)
27K9	5,476,802	12/19/95	Yamazaki et al.	—	—	
27K9	5,716,871	02/10/98	Yamazaki et al.	—	—	
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Document Number	Date	Country	Class	Subclass	Translation Yes No
5-90159	04/09/93	Japan	—	—	Abst.

OTHER DOCUMENTS (Including Author, Title, Relevant Pages, Date, Place of Publication)

Examiner

G. MUNSON

Date Considered

14 DECEMBER 2000

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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Serial No. ^{239/948} Not Yet Assigned

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Applicant: Shunpei YAMAZAKI et al.

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U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date (if appropriate)
<i>SKH</i>	5,569,615	10/29/96	Yamazaki et al.	437	43	
<i>SKH</i>	4,780,424	10/25/88	Holler et al.	437	43	
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<i>SKH</i>	Sameshima et al., "XeCl excimer laser annealing used to fabricate poly-si TFTs", Mat. Res. Soc. Symp. Proc., Vol. 71, 1986, pp. 435-440
<i>SKH</i>	Corey et al., "A shallow junction submicrometer PMOS process without high temperature anneals", IEEE electron device letters, Vol. 9, No. 10, Oct. 1988, pp. 542-544
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Examiner *G. Munson*Date Considered *14 DECEMBER 2000*

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